

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants:

YOSHIDA, et al

Serial No.:

Rule 1.53(b) continuation of U.S. Patent

Application Serial No. 09/581,814, filed June

19, 2000

Filed:

Herewith

For:

ABRASIVE METHOD OF POLISHING TARGET MEMBER AND

PROCESS FOR PRODUCING SEMICONDUCTOR DEVICE

Group of parent:

3723

Examiner of parent: D. Nguyen

## UNDER 37 CFR §1.97 AND §1.98

Assistant Commissioner for Patents Washington, D.C. 20231 Sir:

January 11, 2002

Pursuant to Applicants' duty of disclosure, enclosed please find a List of documents cited in prior application Serial No. 09/581,814, filed June 19, 2000.

Since application Serial No. 09/581,814 is being cited under 35 USC §120 in the above-identified Continuation application, copies of the listed documents are not enclosed. See 37 CFR §1.98(d).

To the extent that the above-listed documents are not English, the requirements of 37 CFR §1.98(a)(3) are satisfied at least by the English translations enclosed with the documents as submitted in prior application Serial No.

09/581,814.

This Information Disclosure Statement is being submitted concurrently with the filing of the above-identified Continuation application.

In view of all of the foregoing, consideration of the listed documents, upon examination of the above-identified application, is respectfully requested.

Kindly charge any additional fees due, or credit overpayment of fees, to Deposit Account No. 01-2135 (Case No. 566.38683CX1).

Respectfully submitted,

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RTW/RTW Enclosures